

Optics for EUV-Lithography with high NA

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To enable manufacturing of integrated circuits with critical dimension down to 10 nm in lithography tools operating at a wavelength of 13.5 nm the numerical aperture is being increased from 0.33 presently used in mass production to 0.55 for the next generation of systems. We will discuss the challenges in the design and production of the EUV optics and how they have been tackled.